

IN THE ABSTRACT:

Please cancel the current abstract and insert the following. A marked-up copy showing the changes made to the abstract is attached hereto in Appendix A.

-- An exposure apparatus for exposing a substrate using a master. The apparatus includes a stage being able to install a master, a first housing surrounding the stage, a second housing for stocking at least one of the masters, the second housing being allowed to communicate with the first housing, and a third housing being installed between an inside space and an outside space of the first housing, wherein a master is transferred to the first housing and is extracted from the first housing via the third housing. The first and second housings are filled by an inert gas or are adapted to be evacuated. --

IN THE SPECIFICATION:

Please amend the specification as follows:

Please substitute the paragraph beginning at page 1, line 5, with the following. A marked-up copy of this paragraph, showing the changes made thereto, is attached in Appendix A.

-- The present invention relates to an exposure apparatus for exposing a substrate such as a wafer or glass plate coated with a photosensitive agent to a circuit pattern on a master such as a reticle or mask in a lithography step for manufacturing various devices such as a semiconductor element, liquid crystal element, and thin-film magnetic head and, particularly, to a master transfer system for the exposure apparatus. --